The Beams and Applications Seminar Series

Optics Fabrication and Metrology at the APS

Albert Macrander APS, Argonne National Laboratory

Bldg. 401, room B2100 Friday, Feb. 6, 1:30 pm

Host: K.-J. Kim, ASD

The OFM group has as its mission the fabrication and measurement of x-ray optics for APS beamlines. Examples from four areas will be presented: i) fabrication, polishing, and etching of crystal monochromators and analyzers; ii) x-ray topography and x-ray characterization of monochromators and thin film substrates; iii) thin film deposition for grazing incidence mirrors and multilayer optics; iv) metrology of x-ray optics done without using x-rays. Some specialized optics will be discussed including: diamond monochromators, Kirkpatrick-Baez focusing mirrors, multilayer monochromators, and multiple lens designs that are based on x-ray refraction.

Supported by the U.S. DOE, Office of Science, BES, under contract No. W-31-109-ENG-38.

For more information visit

http://www.aps.anl.gov/asd/physics/seminar.html

Visitors from off-site please contact Yuelin Li (ylli@aps.anl.gov, 630-252-7863) to arrange for a gate pass.

This ANL seminar series is a CARA activity and focuses on the physics, technology and applications of particle and photon beams. It is sponsored jointly by the ASD Division, the AWA group of the HEP Division, and the ATLAS group of the PHY Division.